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AMENDMENT TRANSMITTAL LETTER (Large Entity)				Docket No. SEC.910	
Applicant(s): Kyoung-Hwan CHIN et al.					
Serial No. 09/988,302	Filing Date 19 November 2001	Examiner Gentle WINTER		Group Art Unit 1746	
Invention: CLEANING APPARATUS OF A HIGH DENSITY PLASMA CHEMICAL VAPOR DEPOSITION CHAMBER AND CLEANING METHOD THEREOF					
<u>TO THE COMMISSIONER FOR PATENTS:</u>					
Transmitted herewith is an amendment in the above-identified application. The fee has been calculated and is transmitted as shown below.					
CLAIMS AS AMENDED					
	CLAIMS REMAINING AFTER AMENDMENT	HIGHEST # PREV. PAID FOR	NUMBER EXTRA CLAIMS PRESENT	RATE	ADDITIONAL FEE
TOTAL CLAIMS	9 -	20 =	0 x	\$18.00	\$0.00
INDEP. CLAIMS	2 -	3 =	0 x	\$86.00	\$0.00
Multiple Dependent Claims (check if applicable) <input type="checkbox"/>					\$0.00
TOTAL ADDITIONAL FEE FOR THIS AMENDMENT					\$0.00
<input checked="" type="checkbox"/> No additional fee is required for amendment. <input type="checkbox"/> Please charge Deposit Account No. _____ in the amount of _____ <input type="checkbox"/> A check in the amount of _____ to cover the filing fee is enclosed. <input type="checkbox"/> The Director is hereby authorized to charge payment of the following fees associated with this communication or credit any overpayment to Deposit Account No. <input type="checkbox"/> Any additional filing fees required under 37 C.F.R. 1.16. <input type="checkbox"/> Any patent application processing fees under 37 CFR 1.17.					
 _____ Signature			Dated: 24 May 2004		
KENNETH D. SPRINGER REG. NO.: 39,843 VOLENTINE FRANCOS, PLLC 12200 SUNRISE VALLEY DRIVE, SUITE 150 RESTON, VA 20191 TEL. NO.: (703) 715-0870					
I certify that this document and fee is being deposited on _____ with the U.S. Postal Service as first class mail under 37 C.F.R. 1.8 and is addressed to the Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450.					
Signature of Person Mailing Correspondence					
Typed or Printed Name of Person Mailing Correspondence					
CC:					



Serial No. 09/988,302
SEC:910
Amendment dated 24 May 2004

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re PATENT APPLICATION of:

Kyoung-Hwan CHIN et al.

Group Art Unit: 1746

Serial No.: 09/988,302

Examiner: Gentle WINTER

Filed: 19 November 2001

CLEANING APPARATUS OF A
HIGH DENSITY PLASMA
CHEMICAL VAPOR DEPOSITION
CHAMBER AND CLEANING
METHOD THEREOF

AMENDMENT UNDER 35 C.F.R. 1.111

U.S. Patent and Trademark Office
2011 South Clark Place
Customer Window, Mail Stop **Non-Fee Amendment**
Crystal Plaza Two, Lobby, Room 1B03
Arlington, VA 22202

Sir:

In response to the Office Action dated 25 February 2004, the period for response to which extends through 25 May 2004, please amend the above-identified patent application as follows:

Amendments to the Specification begin on page 2 of this paper.

Amendments to the Claims are reflected in the listing of claims which begins on page 3 of this paper.

Remarks begin on page 6 of this paper.